

IN THE CLAIMS

1. - 47. (Canceled)

48. (New) A method for manufacturing an electron source comprising the steps of:

forming a plurality of electroconductive films each having a fissure and being connected to a wiring on a substrate; and

forming, within the fissure of each electroconductive film, a deposit containing carbon as a main ingredient in connection with the electroconductive film,

wherein the step of forming the deposit includes a step of applying a voltage to each of the electroconductive films through the wiring within an atmosphere containing carbon.

49. (New) The method according to claim 48, wherein, in the step of forming the deposit, the deposit containing carbon as a main ingredient is also formed on the electroconductive film.

50. (New) The method according to claim 48, wherein, in the step of forming the deposit, the deposit containing carbon as a main ingredient is formed, within the fissure, to have a gap narrower than the fissure.